Superior uniformity and repeatability with new Uniform FlowFlange® technology

Industry’s highest productivity due to full automation and one-run recovery period after maintenance

Low maintenance TurboDisc® technology enables highest system availability

Production-proven platform offers lowest cost of ownership

Veeco

Solutions for a nanoscale world™
**TurboDisc K465i GaN MOCVD System**

The TurboDisc K465i™ GaN MOCVD System is the newest entry into Veeco’s K-Series platform, which is production-proven and provides high productivity and reduced cost of ownership in HB LED high-volume production fabs around the globe. The K465i achieves up to 90% yield (5nm bin) due to its superior uniformity and excellent run-to-run repeatability. It also offers the industry’s highest productivity due to its full automation and shortened recovery period after maintenance.

At the heart of the TurboDisc K465i GaN MOCVD System is Veeco’s patent-pending Uniform FlowFlange® technology, which was designed to create a uniform alkyl and hydride flow pattern across all wafers. This results in superior uniformity and repeatability with the industry’s lowest particle generation. The FlowFlange’s simplified design provides ease-of-tuning for fast process optimization on wafer sizes up to 8 inches and fast tool recovery time after maintenance for the LED industry’s highest productivity.

**K465i Productivity Advantage**

**MINIMAL MAINTENANCE AND HIGHEST THROUGHPUT**

- Low maintenance TurboDisc technology enables highest system availability and throughput
- Uniform laminar flow provides for clean reactor during all growths
- No daily in-situ bakes needed and no daily or weekly cleaning required

Fully automated, production-proven platform

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**Cost-Saving Extendibility**

**SEAMLESS TRANSITION TO LARGER WAFER SIZES UP TO 8”**

- 12 x 4”
- 3 x 8”

**Superior Wavelength Uniformity**

**CAPABLE OF ACHIEVING 90% YIELD IN 5nm BIN**

- Superior within-wafer uniformity
- Excellent wafer-to-wafer repeatability

![Wavelength uniformity](image)

Wavelength uniformity Standard Deviation: $\lambda = 461$nm with $\sigma = 1.55$nm

Optimal Experiments
Optimal Modeling

Excellent thickness uniformity across wafer carrier

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Find out more at www.veeco.com/mocvd or call 1.888.24.VEECO